

**Notice of References Cited**

Application/Control No.

09/895,198

Applicant(s)/Patent Under

Reexamination  
MULLER ET AL

Examiner

Vikki H Trinh

Art Unit

2814

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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6027968	02-2000	nguyen et al.	438/254
	C	US-			
	D	US-			
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	F	US-			
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Michaelis, A.; Gent, O.; Mantz, U., VLSI TechnologSpectroscopic Anisotropy Micro-Ellipsometry (SAME) for determination of lateral and vertical dimensions of sub-micron lithographic structures, International Symposium, 1999, pp. 131-1
	V	
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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